Develop your custom Photonic Integrated Circuit for Data Centers

Dr. Katarzyna ŁAWNICZUK VP, Bright Photonics BV, Netherlands



virtual conference session: Data Center Interconnects – Towards Mass Manufacturing

online / October 6th 2020 / 4 – 7pm



Develop your custom Photonic Integrated Circuit for Data Centers

Technology selection and design & validation

Katarzyna Ławniczuk k.lawniczuk@brightphotonics.eu

Photonics Days 2020 – Berlin Brandenburg 6 October 2020



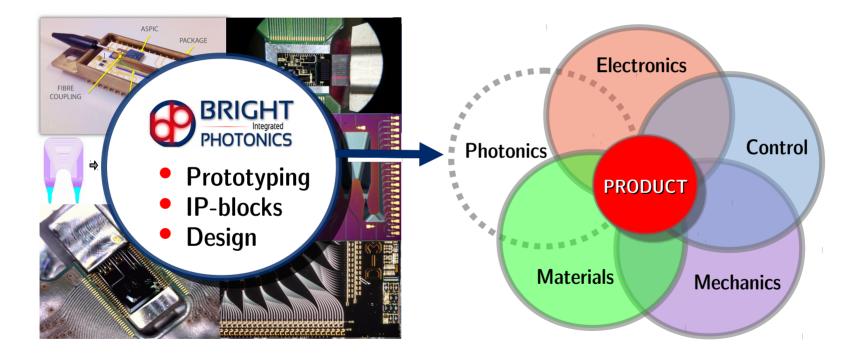
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BRIGHT Photonics B.V. (C)



About BRIGHT Photonics:

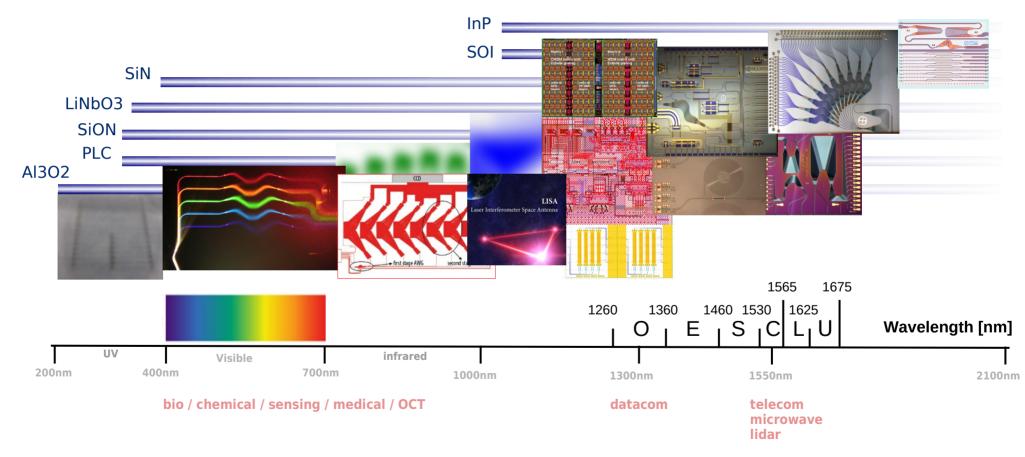
Empowering products with photonic engineering



About BRIGHT Photonics:



Design across wavelengths from UV to IR

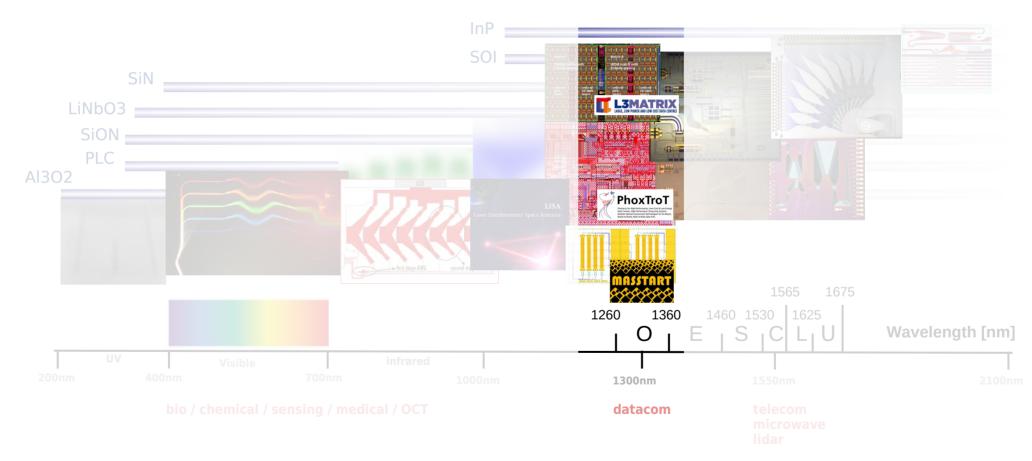


3

About BRIGHT Photonics:

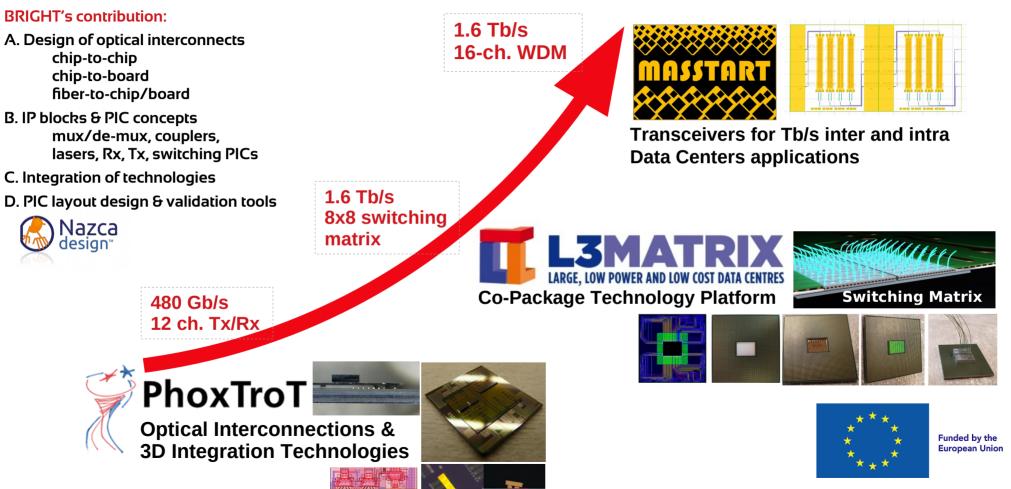


Design across wavelengths from UV to IR



Development beyond 400G in EU projects





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5



4.1 x 3.1 μm² @ 1550nm

Tapered

waveguide

10.8 x 10 µm

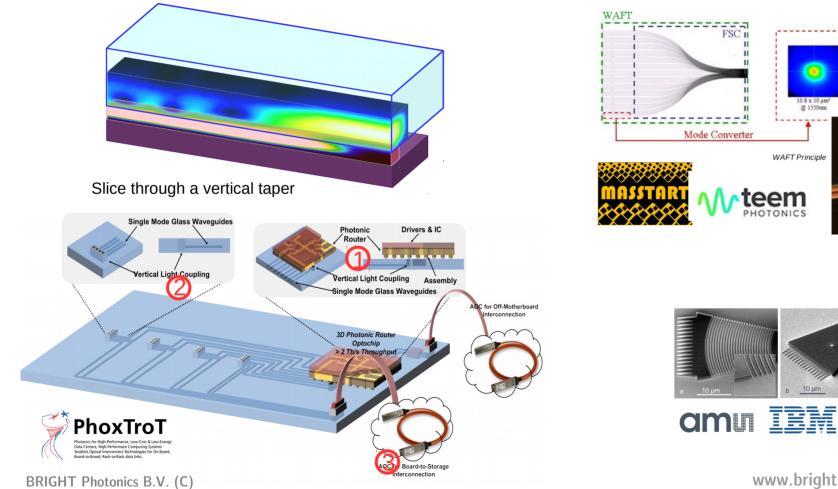
@ 1550nm

10 µm

Confined

waveguide

A. Optical interconnects



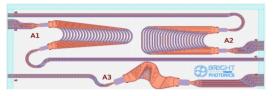
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6

B. IP-blocks and PIC concepts



• Commercial MUX and DeMUX components



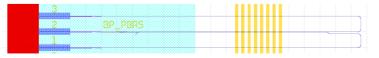
• Lasers (O-band, C-band)



• Spot-size converters



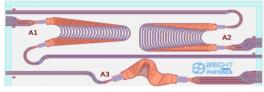
• Polarization handling devices



B. IP-blocks and PIC concepts



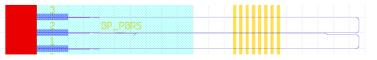
• Commercial MUX and DeMUX components



- Lasers (O-band, C-band)
- Spot-size converters



• Polarization handling devices



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Echelle g	rating	Echelle	grating	
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		AMZI		
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DFB	FP-DBR	DFB		DBR
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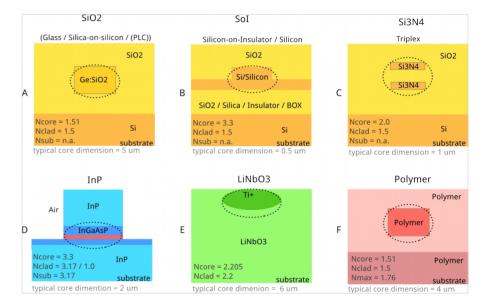
L3Matrix: switching matrix

8



C. Integration technologies: combining (low-loss) passives and actives

→ monolithic vs. hybrid integration



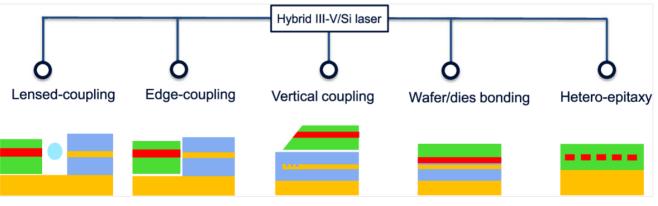
Variety of material platforms

9



C. Integration technologies: combining (low-loss) passives and actives

- → monolithic vs. hybrid integration
- → hybrid III-V/Si laser integration



G. de Valicourt et al., JLT, 36 (2) 2018.

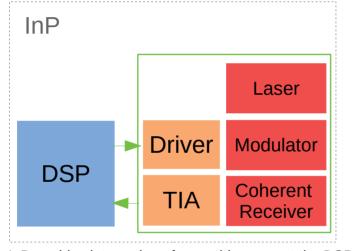


C. Integration technologies: Transceivers always combine InP and Si

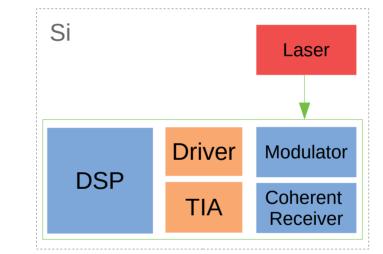
CMOS

SiGe

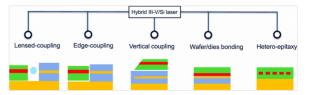
InP



InP enables integration of everything except the DSP



Si enables integration of all electronic and photonic components except the laser



C. Integration technologies: comparison



		InP (generic integration)	SiP with external lasers	Heterogeneous integration (SOI)	Epitaxial growth on Si
Technical	Optical loss		0.1 dB LETI (rib)		
	Active/lasers coupling	0.1 dB butt-join	2-8 dB chip-to-chip	0.5 dB taper loss	0.1 dB butt-join
	Photodiodes				
	Mux/DeMUX				
	Polarization Control				
	Electronics integration				
Production	III-V substrate	1	~	1	-
	III-V growth	1	~	1	1
	SOI/Si substrate	-	1	1	1
	Footprint	High index contrast in 1D	High index contrast in 2D	High index contrast in 2D	High index contrast in 2D
	Yield		CMOS level		
Economic	Substrate cost (\$/cm²)	4.5	0.2	1.5	0.2
	Assembly costs	Fiber coupling	Laser coupling	III-V bonding	Fiber coupling
	Testing	Wafer level	Lasers, SiP	Wafer level	Wafer level
	Wafer size/scaling up	100 mm		300 mm	
Foundries / Product owners		Smart Photonics, Fraunhofer HHI / Infinera, Finisar	VTT, LETI, imec / Luxtera, Rockley	LETI, imec, TU/e - IMOS / Intel	Under research AIM, imec

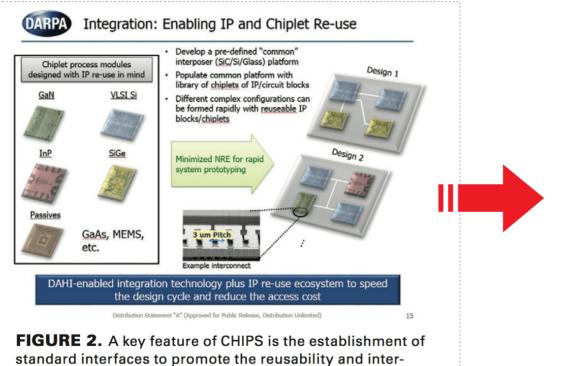
C. Integration technologies: comparison



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	Photodiodes				
	Mux/DeMUX				
	Polarization Cont				
	Electronics integr	Applicat	ion / Spec		
Production	III-V substrate	Volume	ion / Spec	~	-
	III-V growth			~	1
	SOI/Si substrate	Yield		1	1
	Footprint	Cost		th index contrast in 2D	High index contrast in 2D
	Yield			CMOS level	
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C. Integration technologies: Moving towards complex modular systems



changeability of modular circuit functional blocks or chiplets.

Beyond 50000G?

50 GHz bandwidth x 2 symbols per period x 4 bits per symbol (16QAM) x 8 lanes x 8 wavelengths x 2 polarizations

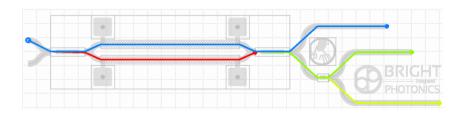
= 51.2 Tb/s

D. Design and validation with Nazca-Design

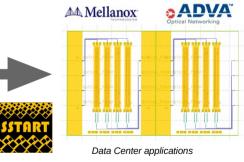




- Combine multiple technologies Hybrid design
 - ➔ Si-Photonics, III-V, Glass
 - ➔ Develop PDK, define and separate technology layers: layers mapping
- Exchange IP Building Blocks IP protection
 - ➔ Combine files and create libraries with GDS BBs, cells mapping
 - → IP BBs handling, work with GDSII standard
 - ➔ Facilitated GDSII files scaling and proper accuracy
- ✓ Solve complex routing and DRC
 - Create interconnects and routing for circuits connectivity with error-free implementation & DRC on connectivity
 - ➔ Path tracing for circuit integrity
- Facilitate new generation of assembly, coupling and packaging approaches
 - ➔ Create packaging rules, packaging templates,
 - ➔ Import fiducials, drivers, tias

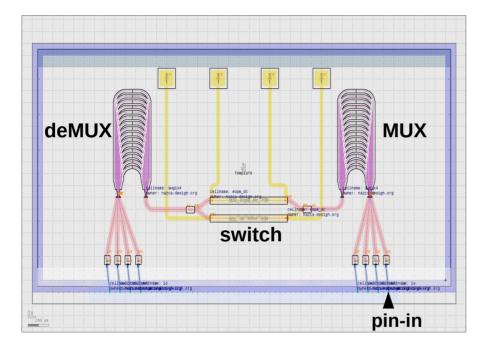


import PDK
import IP BBs
import Packages
import nazca
import leti
import teem
import izm
import ficontec
import bright



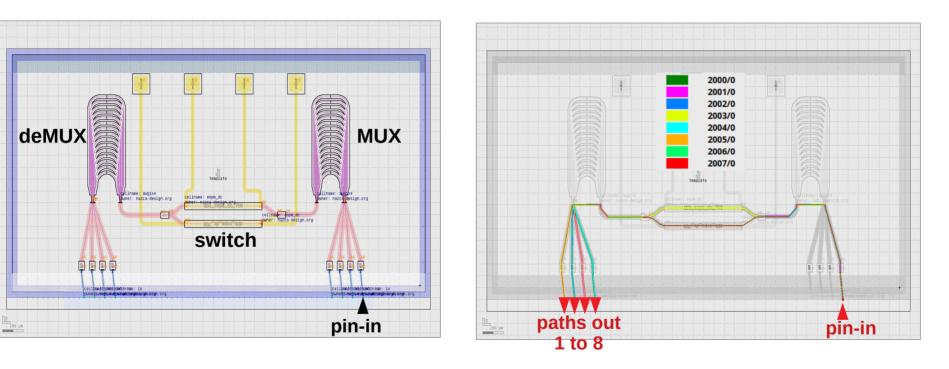
D. Design and validation in GDS







D. Design and validation in GDS: path tracing



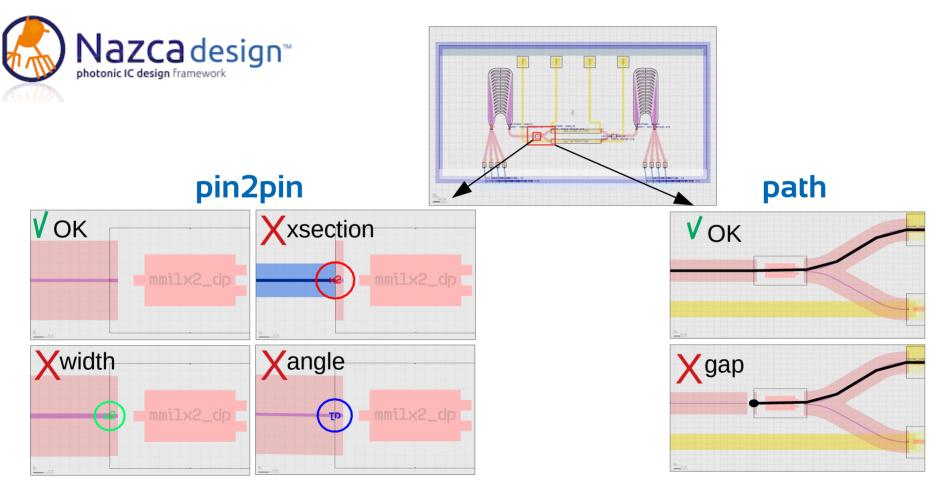


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D. Design and validation in GDS: connection DRC



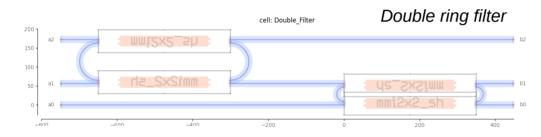


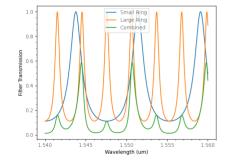
18 BRIGHT Photonics B.V. (C)



D. Design and validation in GDS: circuit simulation and verification at GDS level



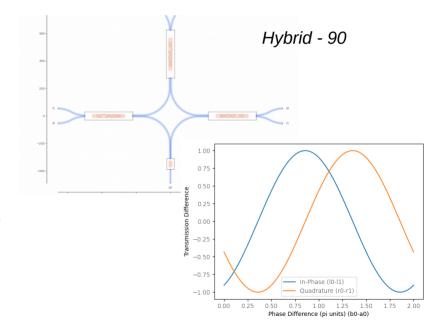




Examples:

- Investigation of filtering characteristics
- Transmission simulation of a circuit
- Integration of Material models in PDK and components S-matrices

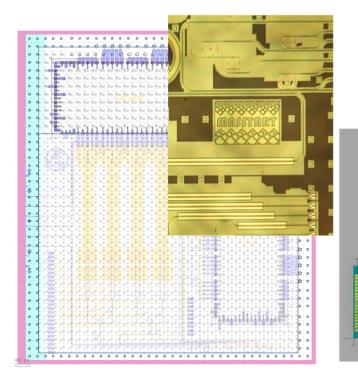




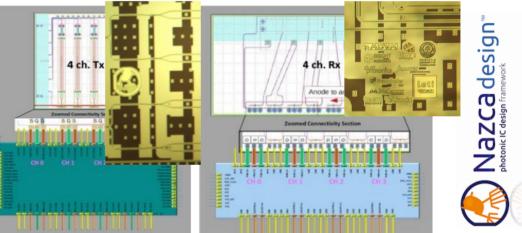
D. Design and validation with Nazca-Design







Tape-out of MASSTART inter- and intra- Data Center PICs





Thank you!

Contact: info@BrightPhotonics.eu

Supply chain development
 PIC concepts & IP blocks
 Prototyping & Design



MASSTART team: Marco Passoni Katarzyna Ławniczuk Ronald Broeke

Acknowledgement



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MASSTART project is an initiative of the **Photonics Public Private Partnership** <u>www.photonics21.org</u>

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Data Center Interconnects - Towards Mass Manufacturing, 6th October 2020

